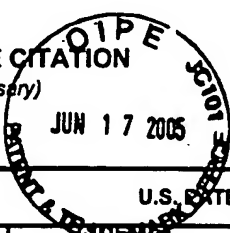


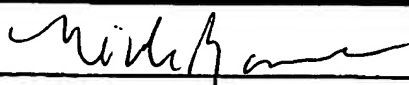
<b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)				ATTY DOCKET NO. 2004US301		APPLICATION NO. 10/808,884	
				APPLICANT(S) Yu SUI et al.			
				FILING DATE March 25, 2004		GROUP ART UNIT 1756	
				U.S. PATENT DOCUMENTS			

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
nm	6,319,651 B1	11/20/2001	Holmes et al.	430	270.1	
	4,491,628	01/01/1985	Ito et al.	430	176	
	5,350,660	09/27/1994	Urano et al.	430	176	
sk	4,863,827	09/05/1989	Jain et al.	430	145	
nm	5,939,236	08/17/1999	Pavelchek et al.	430	273.1	

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nm	2004/0018451 A1	01/29/2004	Choi	430	313	

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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
nm	EP 0 794 458 A2	09/10/1997	EUROPE				
	GB 2 320 718 A	07/01/1998	GREAT BRITAIN				
	DE 30 30 086 A1	03/21/1991	GERMANY				
	DE 39 30 087 A1	03/14/1991	GERMANY				
	DE 41 12 967 A1	10/22/1992	GERMANY				

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sk			Yamaoka et al., "Photochemical Dissociation of p-Nitrobenzyl Aromatic Sulfonate and Its Application to Chemical Amplification Resists", <i>Journal of Photopolymer Science and Technology</i> , Vol. 3, No. 3 (1990), pp. 275 - pp. 280
nm			Schlegel et al., "Studies on the Acid Formation and Deprotection Reaction by Novel Sulfonates in a Chemical Amplification Positive Photoresist", <i>Journal of Photopolymer &amp; Science Technology</i> , Vol. 3, No. 3 (1990), pp. 281 - pp. 287

EXAMINER 	DATE CONSIDERED 8/23/05
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<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>				ATTY DOCKET NO. 2004US301		APPLICATION NO. 10/808,884	
				Yu SUI et al.			
				FILING March 25, 2004		GROUP ART 1756	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
nm	5,886,102	03/23/1999	Sinta et al.	325	154		
	6,110,653	08/29/2000	Holmes et al.	430	325		
	6,080,530	06/27/2000	Shao et al.	430	325		
d	6,251,562 B1	06/26/2001	Breyta et al.	430	287.1		
lm	4,910,122	3/20/1990	Arnold et al.	430	313		

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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	

FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
nm	WO 97/33198	09/12/1997	WIPO				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
nm		Shiral et al., "Photochemistry of Imino Sulfonate Compounds and Their Application to Chemically Amplified Resists", <i>Journal of Photopolymer Science and Technology</i> , Vol. 3, No. 3 (1990), pp. 301 - pp. 304
nm		CRC Handbook of Chemistry & Physics, "Dissociation Constants Of Organic Acids And Bases", CRC Press (1994-1995 75th Edition), pp. 8-45 - pp. 8-55

EXAMINER <i>[Signature]</i>	DATE CONSIDERED 8/23/05
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<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i> <span style="font-size: 1.5em; margin-left: 20px;">6/17/05</span>				ATTY DOCKET NO. 2004US301		APPLICATION NO. 10/808,884		
				Yu SUI et al.				
				FILING March 25, 2004		GROUP ART 1756		
<b>U.S. PATENT DOCUMENTS</b>								
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
hmb		5,635,333	06/03/1997	Petersen et al.	430	311		
		5,882,996	06/16/1999	Dal	438	597		
		6,319,651 B1	11/20/2001	Holmes, et al.	430	270.1		
		6,054,254	04/25/2000	Sato et al.	430	322		
hmb		6,114,085	09/05/2000	Padmanaban et al.	430	270.1		
<b>U.S. PATENT APPLICATION PUBLICATIONS</b>								
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<b>FOREIGN PATENT DOCUMENTS</b>								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>								
		Moon et al., "Three-Component Photopolymers Based on Thermal Cross-Linking and Acidolytic De-Cross-Linking of Vinyl Ether Groups. Effects of Binder Polymers on Photopolymer Characteristics, <i>Chemical Materials</i> , Vol. 6 (1994), pp. 1854 - pp. 1860						
		Abstract of Houlihan et al., "Chemically amplified resists. The chemistry and lithographic characteristics of nitrobenzyl benzenesulfonate derivatives", <i>Journal of Photopolymer &amp; Science Technology</i> , Vol. 3, pp. 259 - pp. 273 (1990)						
EXAMINER <span style="font-family: cursive;">Kirk M...</span>				DATE CONSIDERED <span style="font-family: cursive;">8/23/05</span>				
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>								

<b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)  <span style="font-size: 1.5em;">611105</span>	ATTY DOCKET NO. 2004US301	APPLICATION NO. 10/808,884
	Yu SUI et al.	
	FILING March 25, 2004	GROUP ART 1756

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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
nm	5,652,297	07/29/1997	McCulloch et al.	524	555	
	5,981,145	11/09/1999	Ding et al.	430	271.1	
	6,187,506 B1	02/13/2004	Ding et al.	430	271.1	
	5,939,236	08/17/1999	Pavelchek et al.	430	273.1	
nm	5,935,760	08/10/1999	Shao et al.	430	271.1	

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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

**FOREIGN PATENT DOCUMENTS**

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
					YES	NO

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

nm			Abstract of Yamaoka et al., "Reactions of vinyl ethers and application to photoreactive process", Trends in Photochemistry & Photobiology, Vol. 7, pp. 45 - pp. 70 (2001)
nm			Abstract of Schacht et al., "Acid labile crosslinked units: a concept for improved positive deep-UV photoresists", ACS Symposium Series, 706, pp. 78 - pp. 94 (1998)

EXAMINER <span style="font-size: 1.2em;">[Signature]</span>	DATE CONSIDERED 7/23/05
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# INFORMATION DISCLOSURE CITATION

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11/17/05

ATTY DOCKET NO.  
2004US301

APPLICATION NO.  
10/808,884

Yu SUI et al.

FILING  
March 25, 2004

GROUP ART  
1756

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nm	5,731,386	03/24/1998	Thackeray et al.	525	328.2	
	5,880,169	03/09/1999	Osawa et al.	022	25	
	5,354,643	10/11/1994	Cabrera et al.	430	270.1	
	5,716,756	02/10/1998	Pawlowski et al.	430	270.1	
nm	5,069,997	12/03/1991	Schwalm et al.	430	270.1	

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## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)


EXAMINER

*Mark B...*

DATE CONSIDERED

8/23/05

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<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>  <span style="font-size: 1.5em;">6/17/05</span>				ATTY DOCKET NO. <b>2004US301</b>		APPLICATION NO. <b>10/808,884</b>		
				Yu SUI et al.				
				FILING <b>March 25, 2004</b>		GROUP ART <b>1756</b>		
<b>U.S. PATENT DOCUMENTS</b>								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
RM		5,585,219	12/17/1996	Kaimoto et al.	430	270.1		
<b>U.S. PATENT APPLICATION PUBLICATIONS</b>								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<b>FOREIGN PATENT DOCUMENTS</b>								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>								
EXAMINER				DATE CONSIDERED				
				<span style="font-size: 1.5em;">8/23/05</span>				
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